SHIGA7.033APC PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**Applicant** 

Hada et al.

Appl. No.

: 10/557,694

Filed

November 22, 2005

For

RESIN FOR PHOTORESIST

COMPOSITION, PHOTORESIST COMPOSITION AND METHOD

FOR FORMING RESIST

**PATTERN** 

Examiner

Kelly, C.

Group Art Unit

1752

## RESPONSE TO NOTICE OF NON-COMPLIANT AMENDMENT

## Mail Stop Amendment

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## Dear Sir:

In response to the Notice of Non-Compliant Amendment mailed January 16, 2007, enclosed herewith is a revised preliminary amendment. The preliminary amendment filed on November 22, 2005, was considered non-compliant because the paragraph added at page 1 of the specification was underlined. The enclosed preliminary amendment is the same as the one submitted on November 22, 2005, except that the underlining in the added paragraph has been removed. Thus, no new matter has been added. This preliminary amendment is now compliant, and entry thereof is respectfully requested.

Appl. No.

: 10/557,694

Filed

.

November 22, 2005

No fee is believed to be due. However, please charge any necessary fees to Deposit Account 11-1410. Should there be any questions concerning this application, the Examiner is respectfully invited to contact the undersigned at the telephone number appearing below.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 1/25/07

By:

/: \_\_\_\_/

Neil S. Bartfeld, Ph.D.

Registration No. 39,901

Agent of Record

Customer No. 20,995

(619) 235-8550

3331038 012207